

35 USC §102(b) as being anticipated by Konuma (US 6,127,279). This rejection is respectfully traversed.

In particular, Applicants respectfully submit that the Examiner's rejection is improper. In the rejection, the Examiner contends that Konuma teaches the claimed invention but merely recites the claim elements without any showing or information on where in the reference these claimed elements are allegedly shown. In fact, the only citations to the reference relates to a claim element which the Examiner admits is not shown. This is improper.

37 CFR 1.104(c) states:

(2) In rejecting claims for want of novelty or for obviousness, the examiner must cite the best references at his or her command. When a reference is complex or shows or describes inventions other than that claimed by the applicant, the particular part relied on must be designated as nearly as practicable. The pertinence of each reference, if not apparent, must be clearly explained and each rejected claim specified.

The Examiner has not done this. As a result, Applicants are at a loss as to how to respond to this rejection. Applicants do not know how the Examiner is interpreting the reference or where he believes the claimed elements are shown. Hence, Applicants have no way of knowing if the Examiner's rejection is correct or not and how to rebut it.

Accordingly, the rejection of the claims is improper, and it is respectfully requested that the Examiner issue a new Office Action with more information and specific designations and citations to the reference supporting his rejection or withdraw the rejections.

In addition, in the rejection of independent Claim 11, the Examiner contends that the undeveloped portions of the resist correspond to the claimed patterned resist mask. However, in independent Claim 11, a patterned resist mask is formed over the *semiconductor film*; said semiconductor film is patterned to form at least one *semiconductor island*; and then the patterned

resist mask *located over said semiconductor island is removed* (emphasis added). Hence, it is clear in the claimed method that the patterned resist mask has been developed before patterning the semiconductor film, where the resist mask is patterned by using a photolithographic method. It is known to those skilled in the art that patterning a resist by using a photolithographic method includes the steps of coating, exposure, **development**, etc.

Hence, the Examiner's contention is incorrect, and the rejection of the claims fails.

Claims 19-22 and 36

The Examiner also rejects Claims 19-22 and 36 under 35 USC §102(b) as being anticipated by Chiyou et al. (JP 11-016866). This rejection is also respectfully traversed.

More specifically, the Examiner contends that Chiyou teaches forming at least one semiconductor island over said substrate by patterning the crystallized semiconductor film (citing Drawing 3 of Chiyou in support thereof). However, as Applicants previously explained, drawing 3 does not teach forming a semiconductor island. Instead, drawing 3 shows a water drop on an amorphous silicon surface (see 3A), or a water mark on an amorphous silicon surface (see 3B). See e.g. [0008] in Chiyou.

In order to make this clear, Applicants previously directed the Examiner's attention to US 6,235,122 (Zhang et al.). Applicants had submitted the '122 patent in an IDS on May 29, 2002 which the Examiner reviewed, initialed the 1449 but did not rely upon to reject the claims of the present application. See Office Action of July 5, 2002. As shown in Exhibit A (Family List of JP 11-016866 published by the EPO) attached with the prior response, US 6,235,122 is in the family of JP 11-016866. Once the Examiner has reviewed the '122 patent, it will be clear that Figs. 3, 3B do not teach forming at least one semiconductor island..., but teach a water drop or water mark. Hence,

these figures are not relevant to the claimed invention. Applicants previously pointed this out to the Examiner but no response or explanation to these points was provided in the Office Action. It is respectfully requested that the Examiner issue a new office action which addresses these previously made points.

In addition, in the Office Action, the Examiner lists the claim elements of independent Claim 19 of the present application but fails to show where all the claimed elements are allegedly shown in the reference. As explained above, this is improper.

Also for the reasons explained above for Claim 11, the rejection of Claim 19 (i.e. unwanted portions of the resist mask are removed) also fails.

Accordingly, it is respectfully submitted that this rejection is improper, and it is respectfully requested that either a new complete rejection be issued or the rejection be withdrawn.

Conclusion

Accordingly, the present application is in a condition for allowance and should be allowed.

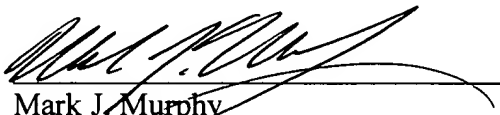
Please charge Deposit Account No. 50-1039 for any fee due for this amendment.

Favorable reconsideration is earnestly solicited.

Respectfully submitted,

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